Amdt. Dated February 27, 2009

Reply to Final Office Action of November 28, 2008

REMARKS

Attorney Docket No. 81844.0048

Customer No.: 26021

This application has been carefully reviewed in light of the Office Action dated

November 28, 2008. Claims 1-9 remain in this application. Claim 1 is the independent

Claim. Claim 1 has been amended. Claim 9 is the new Claim. It is believed that no

new matter is involved in the amendments or arguments presented herein.

Reconsideration and entrance of the amendment in the application are

respectfully requested.

Art-Based Rejections

Claims 1-4 were rejected under 35 U.S.C. § 102(b) as being anticipated by U.S.

Patent No. 4,776,894 (Watanabe); Claims 5 and 7 were rejected under 35 U.S.C.

§ 103(a) as obvious over Watanabe in view of U.S. Patent No. 4,926,230 (Yamagishi);

Claims 6 and 8 were rejected as obvious in view of Watanabe in view of Japanese

Publication JP-59035016 (Nakamura).

Applicant respectfully traverses the rejections and submits that the claims herein

are patentable in light of the clarifying amendments above and the arguments below.

The Watanabe Reference

Watanabe is directed to a first and second photovoltaic cell 3 and 4 each having

a p-i-n structure to form a tandem p-i-n/p-i-n (or n-i-p/n-i-p) structure (See, Watanabe;

Col. 4, lines 17-34). A back electrode 5 and n-type layer 43 are disposed on a i-type

layer 41 of the second photovoltaic cell 4 (See, Watanabe; Fig. 1).

The Yamagishi Reference

Yamagishi is directed to a photovoltaic device of amorphous or microcrystalline

semiconductor having a multijunction (See Yamagishi; Abstract).

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The Nakamura Reference

Nakamura is directed to a hydrogen-containing silicon layer (See Nakamura:

Abstract).

The Claims are Patentable Over the Cited References

The present application is generally directed to a silicon based thin film solar cell.

As defined by amended independent Claim 1, a silicon based thin film solar cell

is provided. A conducted type silicon based low refractive index layer, a silicon based

interface layer, and a back electrode are disposed and contact one another in this order

on a backside of a photoelectric conversion layer observed from a light incident side.

The applied references fail to disclose or suggest the above features of the

claims of the present invention. In particular, the applied references fails to disclose or

suggest "a conducted type silicon based low refractive index layer, a silicon based

interface layer, and a back electrode are disposed and contact one another in this order

on a backside of a photoelectric conversion layer observed from a light incident side,"

as required by amended independent Claim 1 of the present invention.

Watanabe discloses a first and second photovoltaic cell 3 and 4 each having a p-

i-n structure (See Watanabe; Col. 4, lines 17-34). In Fig. 12, back electrode 5 is

separated from a n-type impurity layer 64 and p-type impurity layer 74 by optically active

layer 71 and layers 72 and 73.

In contrast, the present invention requires the low refractive index layer, silicon

based interface layer and back electrode to contact one another on the backside of a

photoelectric conversion layer observed from a light incident side. This feature provides

a silicon based thin film solar cell that exhibits a sufficient light trapping effect to keep a

series resistance of the solar cell small even if a layer having a low refractive index is

disposed (See Specification; Page 7, lines 11-20). Furthermore, the interface layer

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improves a contact resistance between the low refractive index layer and a back

electrode (See Specification; Page 2, lines 9-22).

Moreover, one of ordinary skill in the art would appreciate that a modification of

the Watanabe reference according to the present claims would render that reference

unsuitable for its intended purpose, and/or principle of operation would be changed

(MPEP §2143.01 V, VI).

Watanabe teaches an impurity doped layer of one unit photovoltaic cell which is

located at the contact interface with an adjacent unit photovoltaic cell (See Watanabe,

claims 1, 9). One of ordinary skill in the art would appreciate that impurity layers of

Watanabe (See, Watanabe, Fig. 12, reference numerals 64 and 74) must be located at

the contact interface of two photovoltaic cells and thus cannot contact the back

electrode. The impurity layers of Watanabe shows wider band gap so that the layers

show lower absorption of light and the photovoltaic efficiency can be accordingly

improved (See, Watanabe, Col.1, lines 60-68 and Col. 1, line 66 to Col. 2, Line 11),

One of ordinary skill in the art would realize that such desired effect can be achieved

only if the impurity layers are located at incident side of at least one photovoltaic cell

unit.

Thus, Watanabe does not disclose or suggest the above feature of the present

invention as required by amended independent Claim 1. The ancillary references do

not remedy the deficiencies of Watanabe.

Since the applied reference fails to disclose, teach or suggest the above features

recited in amended independent Claim 1, that reference cannot be said to anticipate nor

render obvious the invention which is the subject matter of that Claim.

Accordingly, amended independent Claim 1 is believed to be in condition for

allowance and such allowance is respectfully requested.

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The remaining claims depend either directly or indirectly from amended

independent Claim 1 and recite additional features of the invention which are neither

disclosed nor fairly suggested by the applied references and are therefore also believed

to be in condition for allowance and such allowance is respectfully requested. For

example, new dependent Claims 9 and 10 recite the refractive index layer and interface

layer to be of a single cell and of the same conductivity type. Neither feature is

disclosed or suggested by Watanabe. Thus, Applicant submits that new Claims 9 and

10 further distinguishes the present invention over the art of record.

Conclusion

Applicant believes the foregoing amendments comply with requirements of form

and thus may be admitted under 37 C.F.R. § 1.116(b). Alternatively, if these

amendments are deemed to touch the merits, admission is requested under 37 C.F.R.

§ 1.116(c). In this connection, these amendments were not earlier presented because

they are in response to the matters pointed out for the first time in the Final Office

Action.

Lastly, admission is requested under 37 C.F.R. § 1.116(b) as presenting rejected

claims in better form for consideration on appeal.

In view of the foregoing, it is respectfully submitted that the application is in

condition for allowance. Reexamination and reconsideration of the application, as

amended, are requested.

If for any reason the Examiner finds the application other than in condition for

allowance, the Examiner is requested to call the undersigned attorney at the Los

Angeles, California telephone number (310) 785-4721 to discuss the steps necessary

for placing the application in condition for allowance.

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If there are any fees due in connection with the filing of this response, please charge the fees to our Deposit Account No. 50-1314.

Respectfully submitted,

HOGAN & HARTSON L.L.P.

Date: February 27, 2009

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